

<p style="text-align: center;">U.S. Department of Commerce, Patent and Trademark Office</p> <p style="text-align: center;">O I P E FEB 03 2004 SEARCHED INDEXED MAILED</p> <p style="text-align: center;">LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary)</p>					Docket No.: 6353/P1/DSM/LOW K/JW		Serial No.: 10/759,801																																																																																																													
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U.S. Patent Documents

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W	AA	5,655,110	08/05/97	Krivokapic et al.	716	19	
	AB	5,657,254	08/12/97	Sierk et al.	702	98	
	AC	5,866,437	02/02/99	Chen et al.	438	14	
	AD	5,917,919	06/29/99	Rosenthal	381	71.11	
	AE	5,926,690	07/20/99	Toprac et al.	439	17	
	AF	6,161,054	12/12/00	Rosenthal et al.	700	121	
	AG	6,197,604 B1	03/06/01	Miller et al.	438	14	
	AH	6,208,751 B1	03/27/01	Almogy	382	149	
	AI	6,230,069 B1	05/08/01	Campbell et al.	702	121	
	AJ	6,245,581 B1	06/12/01	Bonser et al.	438	8	
	AK	6,284,622 B1	09/04/01	Campbell et al.	438	424	

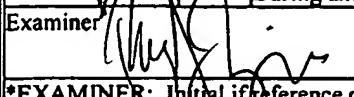
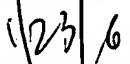
Foreign Patent Documents

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W	AL	3142929A2	06/18/91	Japan			Abstract Only	
	AM	4217456	08/07/92	Japan			Abstract Only	
	AN	569311A	03/23/93	Japan			Abstract Only	
	AO	639704A	02/15/94	Japan			Abstract Only	
W	AP	WO 98/02910	01/22/98	PCT				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

W	AR	IBM Technical Disclosure Bulletin: "Auto-Defect Detection/Visual Defect Review Inspection System," Feb. 1989, pp. 306-307
	AS	IBM Technical Disclosure Bulletin: "Dual Microscope Semiconductor Wafer Inspection Machine," March 1989, pp. 474-479
	AT	IBM Technical Disclosure Bulletin: "Integrated Semiconductor Processing Facilitation by Mobile Ion Gettering During and After Resist Strip," May 1989, pp. 295-297

Examiner  Date Considered 

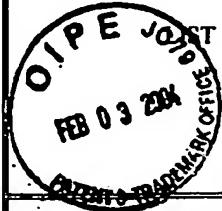
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	AT	The Novascan 210, "Integrated On-Line Thickness Monitoring System for CMP Applications", downloaded from http://www.nova.co.il.scan.htm on 9/10/96																																																																																																																		
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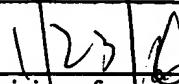
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10	AL	EP 0932 194 A1	07/28/99					
10	AM	WO 00/79355 A1	12/28/00					
10	AN	WO 02/04886 A1	01/17/02					
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

10	AR	J. Bruchez et al., "Linking European Suppliers with Global Users," Semiconductor International, March 1998
10	AS	J. Baliga, "MES and CIM: At the Center of Productivity," Semiconductor International, July 1998
10	AT	A. Braun, "Inspection, Measurement & Test," Semiconductor International, August 1998

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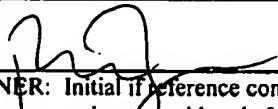
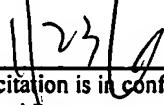
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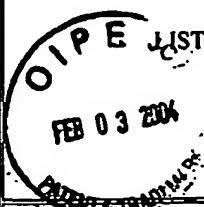
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	AS	Applied Materials Press Release Archive 1998 "Applied Materials Announced First Process Sequence Integration Product: The Copper Interconnect ESS," downloaded from http://www.appliedmaterials.com/newsroom/pr-00169.html on 3/12/02
	AT	J. Fraser, "Treating Software Strategically: Beyond Traditional MES," Semiconductor International, January 1999

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	AT	J. Baliga, "How Advanced Are We?," Semiconductor International, July 1999

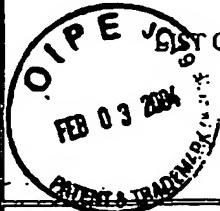
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	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

105	AR	A. Braun, "Metrology Hits the Road to Integration," Semiconductor International, April 2000
111	AS	T. Zavecz et al., "Life Beyond Mix-and-Match: Controlling Sub-0.18 um Overlay Errors", Semiconductor International, July 2000
112	AT	F. Poag et al., "Implementing on-line ADC and an Automated Yield Information Management System," MICROMagazine.com, July, 2000

Examiner  Date Considered

1/23/04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.



U.S. Department of Commerce, Patent and Trademark Office

LIST OF RELEVANT ART CITED BY APPLICANT
 (Use several sheets if necessary)

 Docket No.: 6353/DSM/LOWK/JW
 Serial No.: 10/759,801

Applicant(s):

Howard Li, et al.

 Filing Date: January 16, 2004
 Group: 1763
 Unknown

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
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	AK						

Foreign Patent Documents Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>Wu</i>	AR	A. Toprac et al., "Run-to-Run Control of Shallow Trench Isolation Etch," AEC/APC 2000
<i>Wu</i>	AS	N. Patel, "Mix Issues in Process Control," Sematech AEC/APC Symposium XII, September 25, 2000
<i>Wu</i>	AT	J. Holden et al., "Characterizing a CVD-Integrated Metrology System," Semiconductor International, October 2000

Examiner *Wu* Date Considered *1/23/04*

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U.S. Department of Commerce, Patent and Trademark Office		Docket No.:	Serial No.:
		6353/P1/DSM/LOW K/JW	10/759,801
O I P E LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary)		Applicant(s):	
		Howard Li, et al.	
		Filing Date:	Group: <u>1763</u> January 16, 2004 Unknown

U.S. Patent Documents							
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	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents							Translation	
		Document Number	Date	Country	Class	Subclass	Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<u>HL</u>	AR	A. Braun, "IMA Continues Important APC Standards Work," Semiconductor International, December 2000
<u>HL</u>	AS	L. Peters, "Yield Management Motorola and Infineon Improve APC Strategy," Semiconductor International, February 2001
<u>HL</u>	AT	"Applied Materials Leads the Industry with Process Module Approach for Nanometer Generation Chipmaking Data Validates Groundbreaking Concept," San Francisco (Business Wire) July 16, 2001

Examiner 	Date Considered	123 6
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U.S. Patent Documents

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AA							
AB							
AC							
AD							
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Foreign Patent Documents

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	AL							
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>HL</i>	AR	Nanometrics' NanoSpec 9000 Series Integrated Metrology Systems, downloaded from http://www.nanometrics.com/ProductsIntegrated.htm on 9/17/01
<i>HL</i>	AS	"Applied Materials Launches Industry's First In-Line Metrology SEM System with 3D Imaging," Jan 10, 2000, downloaded from http://www.semiseek.com/News/press_release55.html
<i>HL</i>	AT	Solid State Technology; Claassen-Vujcic et al; "Analysis of a 200/300mm Vertical Furnace with Integrated Technology"; April 2001; pps. s6, s8, s12
Examiner	Date Considered	<u>23</u> <i>Q</i>

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U.S. Department of Commerce, Patent and Trademark Office			Docket No.:	Serial No.:
			6353/P1/DSM/LOW K/JW	10/759,801
LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary) 17			Applicants:	
			Howard Li, et al	
			Filing Date:	Group: 1763
			January 16, 2004	

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
17	US-1	5,408,450	04/18/95	Mozumder et al.	369	44,12	
	US-2	6,004,706	12/21/99	Ausschnitt et al.	430	30	
	US-3	6,213,848 B1	04/10/01	Campbell et al.	700	1	
	US-4	6,148,239	11/14/00	Funk et al.	451	41	
	US-5	6,304,999 B1	10/16/01	Toprac et al.	716	4	
	US-6	6,405,144 B1	06/11/02	Toprac et al.	702	84	
	US-7	6,408,220 B1	06/18/02	Nulman	700	121	
	US-8	6,454,899 B1	09/24/02	Campbell et al.	186	345.24	
	US-9	6,486,492 B1	11/26/02	Su	257	48	
	US-10	6,546,306 B1	04/08/03	Bushman et al.	700	121	
V	US-11	6,587,744 B1	07/01/03	Stoddard et al.	700	121	

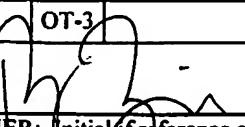
Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
	F-1							
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	OT-1	
	OT-2	
	OT-3	

Examiner  Date Considered **1/23/06**

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				6353/P1/DSM/LOW K/JW	10/759,801
LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary)				Applicants:	
				Howard Li, et al	
				Filing Date: January 16, 2004	Group: 1763

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
jlh	US-12	6,625,497 B2	09/23/03	Fairbairn et al.	700	1	
jlh	US-13	6,625,514 B1	09/23/03	Lensing	700	121	
	US-14						
	US-15						
	US-16						
	US-17						
	US-18						
	US-19						
	US-20						
	US-21						
	US-22						

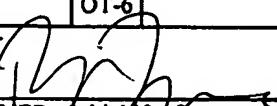
Foreign Patent Documents

Translation

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	F-6							
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	F-9							
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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